

Search Notes

Application No.

10/630,716

Examiner

Stephen W. Smoot

Applicant(s)

FUKUYAMA ET AL.

Art Unit

2813

SEARCHED

| Class | Subclass | Date | Examiner |
|-------|----------|-----------|----------|
| 438 | 623 | 8/20/2004 | SWS |
| 438 | 624 | 6/20/2004 | SWS |
| 438 | 637 | 6/20/2004 | SWS |
| 438 | 638 | 6/20/2004 | SWS |
| 438 | 675 | 8/20/2004 | SWS |
| 438 | 763 | 8/20/2004 | SWS |
| 438 | 780 | 8/20/2004 | SWS |
| 257 | 635 | 8/20/2004 | SWS |
| 257 | 637 | 8/20/2004 | SWS |
| 257 | 642 | 8/20/2004 | SWS |
| 257 | 774 | 8/20/2004 | SWS |
| 257 | 775 | 8/20/2004 | SWS |
| 257 | E23.145 | 8/20/2004 | SWS |
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INTERFERENCE SEARCHED

| Class | Subclass | Date | Examiner |
|-------|----------|------|----------|
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**SEARCH NOTES
(INCLUDING SEARCH STRATEGY)**

| | DATE | EXMR |
|--|-----------|----------------------|
| Key Words: Low Dielectric Constant - Low k, Low Permittivity; Contact Hole, Opening Via; Interconnect - Trace, Line, Wiring; | 8/20/2004 | <i>S.W.S.</i> SWS |
| Interlayer, ILD, IMD - Organic, Porous Silica; Borderless Contact; Transistor - Source, Gate, Drain. | 8/20/2004 | <i>S.W.S.</i> SWS |
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| Search Tools - EAST (attached); USPAT; US PG PUBS; Derwent; EPO; JPO; IBM TDB | 8/20/2004 | <i>S.W.S.</i> SWS |
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